NFORMATION CITED BY APPLICANTS THAT MAY BE MATERIAL TO THE PROSECUTION OF THE SUBJECT APPLICATION

Applicants:

L.W. Graham et al.

Attorney Docket No.: SEMT116060

Application No.: 09/429,446

Group Art Unit:

1734

Filed:

October 28, 1999

Examiner:

W. Leader

Title:

METHOD, CHEMISTRY, AND APPARATUS FOR NOBLE METAL

ELECTROPLATING ON A MICROELECTRONIC WORKPIECE

U.S. PATENT DOCUMENTS

*Examiner		Document		•	
Initial	ID	No.	Date	Name	
wl	U1	4,285,784	08/1981	Flinn et al.	
M	U2	4,358,352	11/1982	Rhoda	西
Wh	U3	4,427,502	01/1984	Abys	RECEIVOLOGY
W2	U4	4,750,977	06/1988	Marrese	FOEW FOLDER
M	Ú5	5,310,475	05/1994	Kitada et al.	EN CE
W	U6	5,421,991	06/1995	Yarita	NED 3 2003 CENTER
W.	U7	5,494,560	02/1996	Arimoto et al.	_R 1700
WL	.U8	5,529,680	06/1996	Kitada et al.	00
wh.	U9	5,620,583	04/1997	Kuhn et al.	• .
Examiner		Date Co	onsidered		
William Leader		3/2	100	·	

^{*}Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. MSK:mc